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INFORMATION DISCLOSURE STATEMENT BY APPLICANT (Use several sheets if necessary)	APPLICANT **Aaron Scott Lukas, et al.**	
(37 CFR 1.98(b))	FILING DATE 7/21/03	GROUP 2813

U.S. PATENT DOCUMENTS

EXAMINER INITIAL		DOCUMENT NUMBER							DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPRO-PRIATE
NB		4	6	0	3	1	6	8	7/29/1986	S. Sasaki, et al.	522	18	2/19/1985
NB		5	6	0	9	9	2	5	3/11/1997	R. C. Camilletti, et al.	427	503	12/4/1995
NB		5	9	7	0	3	8	4	10/19/1999	S. Yamazaki, et al.	438	795	8/2/1995
NB		6	0	1	7	8	0	6	1/25/2000	K. C. Harvey	438	475	7/28/1998
NB		6	0	4	2	9	9	4	3/28/2000	J. Yang, et al.	430	296	1/8/1999
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NB	02	0	1	0	2	4	1	3	8/1/2002	Q. Han, et al.	428	446	7/16/2001
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NB	03	0	0	5	4	1	1	5	3/20/2003	R.Albano, et al.	427	487	9/14/2001

FOREIGN PATENT DOCUMENTS

		DOCUMENT NUMBER							DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION	
													YES	NO
NB	WO	9	7	0	0	5	3	5		World			X	
NB	WO	02	0	6	5	5	3	4		World			X	

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

NB			E. G. Parada, et al., "Improvement of Silicon Oxide Film Properties by Ultraviolet Excimer Lamp Annealing," Applied Surface Science 86, pp. 294-298 (1995).
NB			A. Guo, et al., "Highly Active Visible-Light Photocatalysts for Curing a Ceramic Precursor[1]," Chem Mater. 10, pp. 531-536 (1998).
NB			T. Clark, Jr., et al., "A New Application of UV-Ozone Treatment in the Preparation of Substrate-Supported, Mesoporous Thin Films," Chem. Mater. 12, pp. 3879-3884 (2000).
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NB			A. Hozumi, et al., "Low-Temperature Elimination of Organic Components from Mesostructured Organic-Inorganic Composite Films Using Vacuum Ultraviolet Light," Chem. Mater. 12, pp. 3842-3847 (2000).
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NB			Q. Han, et al., "Ultra Low-k Porous Silicon Dioxide Films from a Plasma Process," IEEE (2001), pp. 171-173.
NB			C. Waldfried, et al., "Single Wafer RapidCuring™ of Porous Low-k Materials," IEEE (2002), pp. 226-228.

EXAMINER Nerna Berezny	DATE CONSIDERED 11-30-04

EXAMINER: Initial citation considered. Draw line through citation if not in conformance and not considered. Includ copy of this form with next communication to applicant.